

	Hits	Search Text	DBs
60	91	((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5 or post\$5develop\$4) same (develop\$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X\$2ray or DUV) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
61	91	((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5 or post\$5develop\$4) same (develop\$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X\$2ray or DUV) near9 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near10 (remain\$3 or residu\$5) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
62	114	((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5 or post\$5develop\$4) same (develop\$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X\$2ray or DUV) near16 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near5 (remain\$3 or residu\$5 or unexposed) near19 develop\$5)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
63	68	(((resist or photoresist) near3 pattern\$4) same (irradiat\$4 or illuminat\$4 or expos\$4) same (remov\$5 or eliminat\$4) same (residu\$5 or remain\$5 or post\$5develop\$4) same (develop\$5 or TMAH)) and ((ultraviolet or UV or VUV or EUV or X\$2ray or DUV) near16 (laser or ablat\$4 or irradiat\$4 or illuminat\$4 or expos\$4) near12 (resist or photoresist) near5 (remain\$3 or residu\$5 or unexposed) near19 develop\$5) and strip\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB